

Papers and events of interest to customers of Fractilia.

SPIE Advanced Lithography Conference, February 21 - 25, 2021

	Paper Number	Title	Presenter
Online			
	11611-72	The unavoidable renaissance of electron metrology in the age of high NA EUV	Gian Lorusso, imec
	11615-3	LER reduction strategies for 20nm pitch EUV self-aligned double patterning (SADP) with self-aligned block (SAB) formation	Eric Liu, et. Al., TEL
	11611-39	Diagnosing and removing CD-SEM metrology artifacts	Chris Mack, et. Al., Fractilia, imec
	11609-39	Measuring and analyzing contact hole variations in EUV lithography	Chris Mack, et. Al., Fractilia, imec
	11609-28	Performance of stacked nanosheet gate all around FET's with EUV patterned gate sheets	Indira Seshadri, et. Al., IBM, Fractilia
Wednesday			
3:00pm Pacific	Zoom	Tutorial: Using the Power Spectral Density to Understand Roughness	Chris Mack